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## EXPOSURE METHOD AND APPARATUS

**Publication Number:** 2005-142599 (JP 2005142599 A) , June 02, 2005

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**Application Number:** 2005-043679 (JP 200543679)

**Application Number:** 2002-123268

**Application Number:** JP 2002123268 , February 21, 2005

**Priority:**

- 2001-369393 [JP 2001369393], JP (Japan), December 03, 2001
- 2001-126759 [JP 2001126759], JP (Japan), April 24, 2001

**International Class:**

- H01L-021/027
- G03F-007/20

**Abstract:**

**PROBLEM TO BE SOLVED:** To provide an exposing method and an apparatus which enable the exposure of a pattern of contact holes in high resolution (i.e., as for a column of contact holes, the equivalent resolution as an L & S pattern using a phase shift mask) without changing a mask, which has fine hole diameters (e.g.,  $\leq 0.15 \mu\text{m}$ ) and is mixed with contact holes varying from a contact hole or an isolated contact hole to the columns of contact holes. **SOLUTION:** A subject to be exposed is exposed by lightning a mask having a pattern of contact holes and an auxiliary pattern smaller than the pattern of contact holes with a light that forms an effective light source having an empty center of non circular shape, and projecting the pattern of contact holes on the subject to be exposed using a projecting optical system.

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Dialog® File Number 347 Accession Number 8394339